

## P. ARGITIS

### LIST OF PUBLICATIONS AND PATENTS

#### a. JOURNAL PUBLICATIONS

1. P. Argitis, and E. Papaconstantinou, "Photocatalytic Multielectron Photoreduction of 18-Tungstodiphosphate in the Presence of Organic Compounds - Production of Hydrogen", **J. Photochem.**, **30**, 445-451, 1985.
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## b. BOOK CHAPTERS

1. E. Papaconstantinou, P. Argitis, D. Dimotikali, A. Hiskia, and A. Ioannidis, "Photocatalytic Oxidation of Organic Compounds with Heteropoly Electrolytes. Aspects on Photochemical Utilization of Solar Energy" **NATO ASI Series C 174, "Homogeneous and Heterogeneous Photocatalysis"**, E. Pelizzeti and N. Serpone (eds.), Reidel Publishing Co., 1986, pp. 415-431. E.
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### c. PUBLICATIONS IN CONFERENCE PROCEEDINGS

1. P. Argitis, R.A. Srinivas, J.C. Carls, and A. Heller, "Tungsten Nucleated Micropatterns and Via-Hole Walls Formed of Polytungstic Acid Containing Resist", **Materials Research Society Proceedings, Advanced Metallization for ULSI Applications, ULSI-VII, 1992, pp 159-165.**
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